

PATENT

N THE UNITED STATES PATENT AND TRADEMARK OFFICE

| Applicant | : | Fukuda et al. |) | Group Art Unit 1763 | | | |
|-----------|---|---|---------|---------------------|-----------|--------|---|
| Appl. No. | : | 09/511,934 |) | • | | | |
| Filed | : | February 24, 2000 |) | | | | |
| For | : | THIN-FILM FORMING APPARATUS HAVING AN AUTOMATIC CLEANING FUNCTION FOR CLEANING THE INSIDE |)))) | | TC. | | |
| Examiner | : | R. Kackar |) | - - | 1700 | SEP 25 | , |
| | | AMENDMENT AFTER F | IN A | AT. | 1700 MAIL | 25 20 | |

Assistant Commissioner for Patents

Washington, D.C. 20231

Dear Sir:

In response to the Office Action mailed July 1, 2002 (Paper number 8), please amend the above-captioned application as follows:

IN THE CLAIMS:

Please amend Claim 1 as follows:

1. (Twice amended) Athin film forming apparatus comprising:

a reaction chamber for forming at a film formation temperature a thin film on a workpiece placed on a susceptor provided in the reaction chamber, said susceptor being made of aluminum nitride and provided with a heater for heating the workpiece, said reaction chamber being provided with a conveyer for loading and unloading the workpiece into and from the reaction chamber; and

a cleaning device for cleaning unwanted deposits adhering to the inside of the reaction chamber at predetermined intervals, said cleaning device comprising: